

Development of Thick-GEMs for GEM-TPC Tracker

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goal: gain $\sim 10^4$ with stable operation in P10 @ NTP

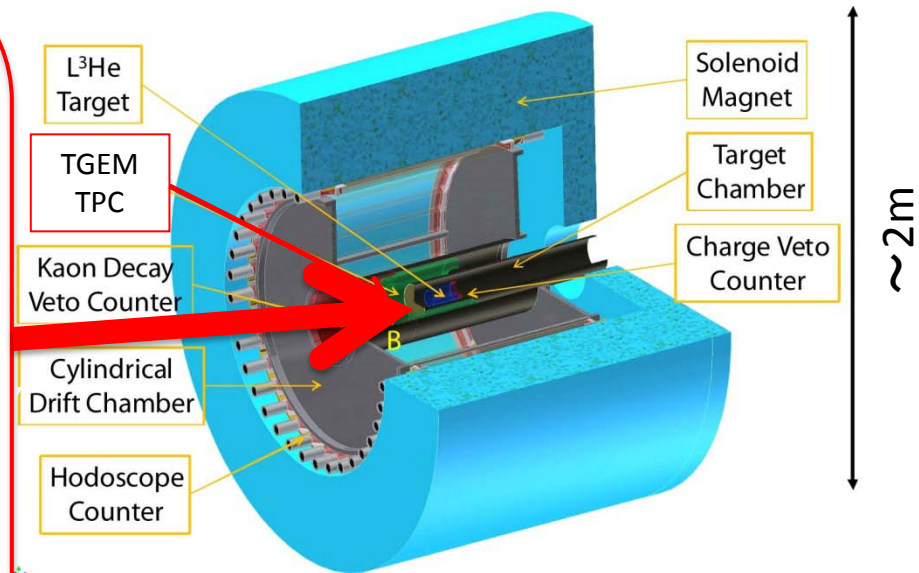
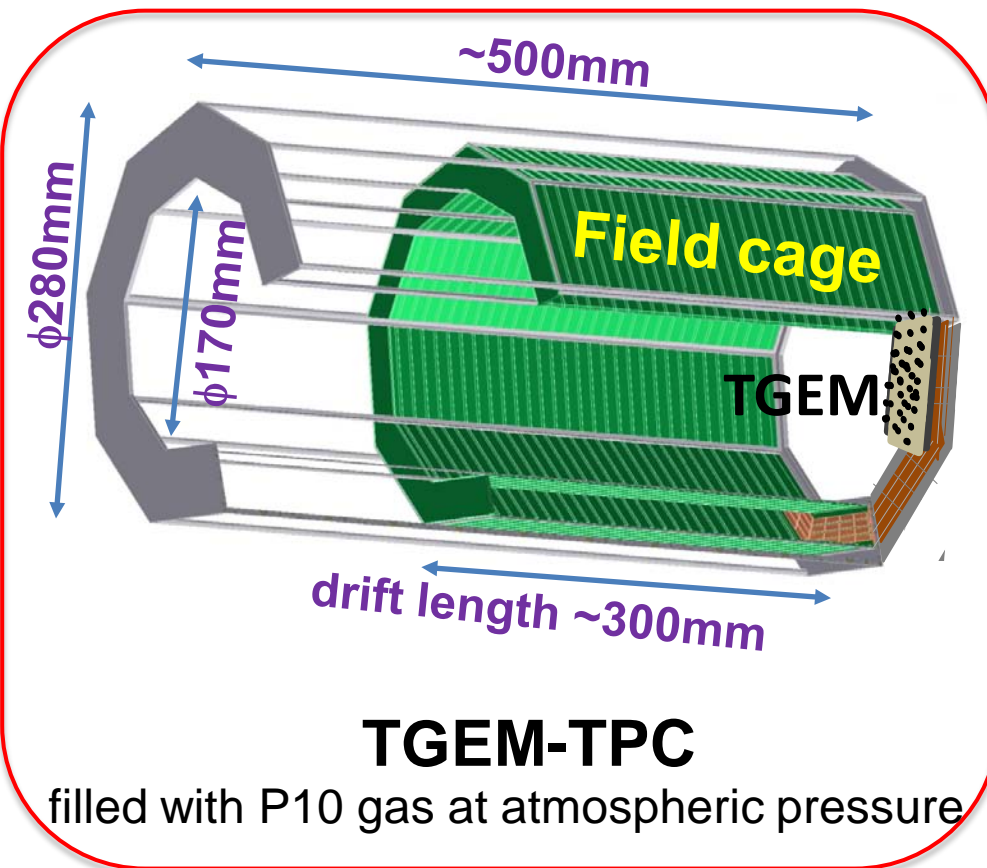
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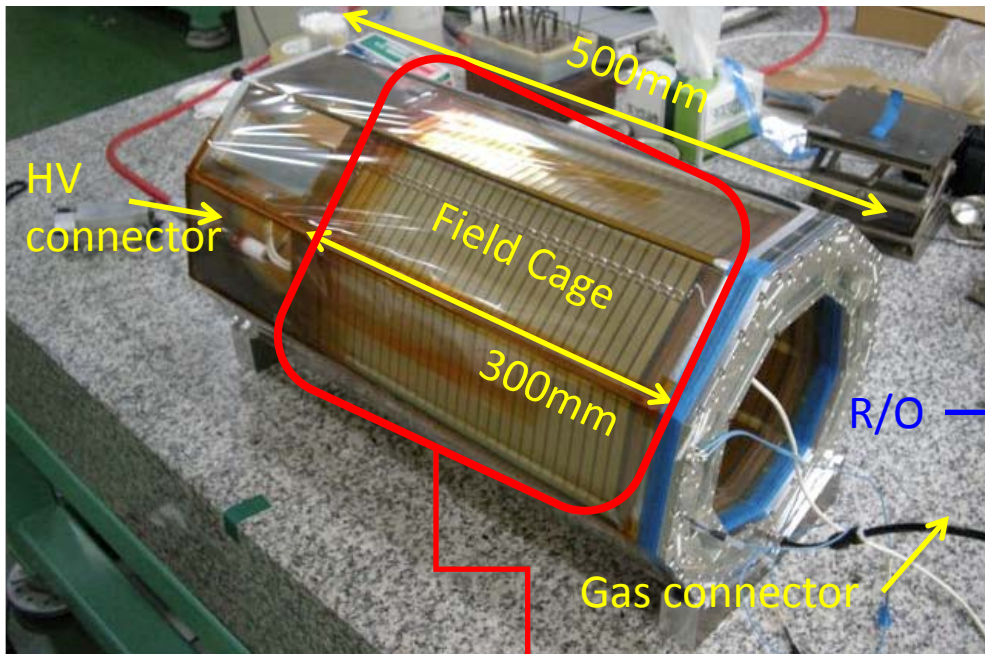
- **Summary**

TGEM-TPC for the J-PARC E15 exp.

- The E15 exp. searches for kaonic nuclei, K^-pp
- missing mass from ${}^3\text{He}(1 \text{ GeV}/c K^-, n)K^-pp$ reaction, and invariant mass from $K^-pp \rightarrow \Lambda + p$ decay
- TGEM-TPC is located at the center of Cylindrical Detector System

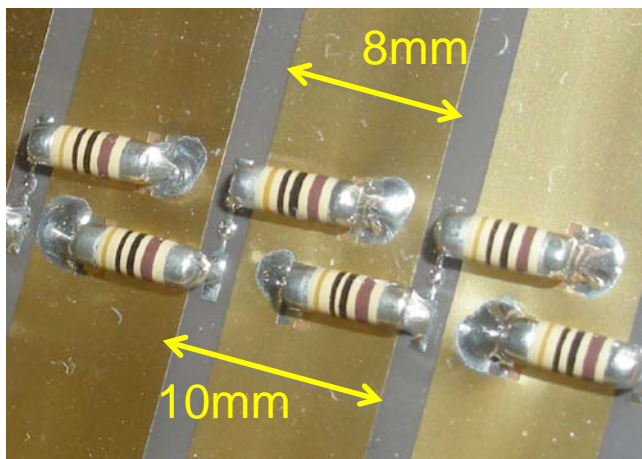


completed TGEM-TPC

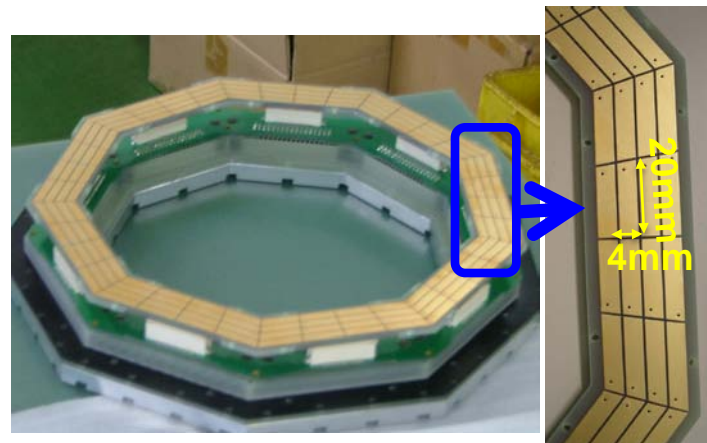


field strip

- double sided
- FPC
- 8mm strip
- 10mm pitch

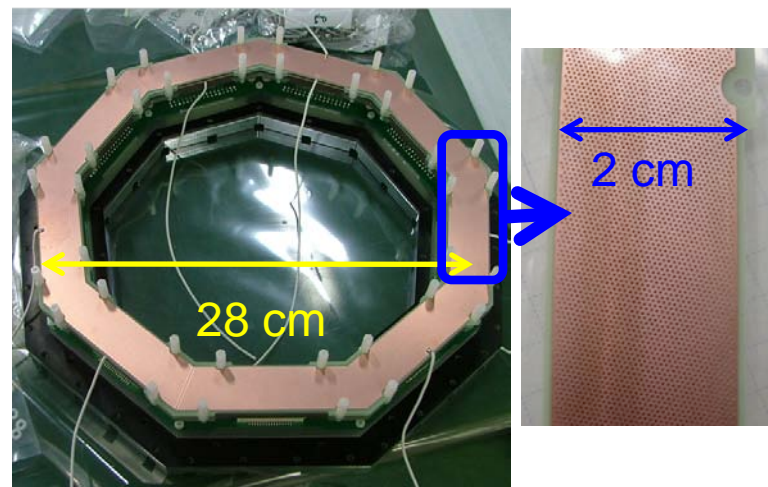


R/O pad size $4\text{mm} \times 20\text{mm}$



of pad = $4 \times 4 \times 9 = 144$

TGEM



non-necessity of support-structure!

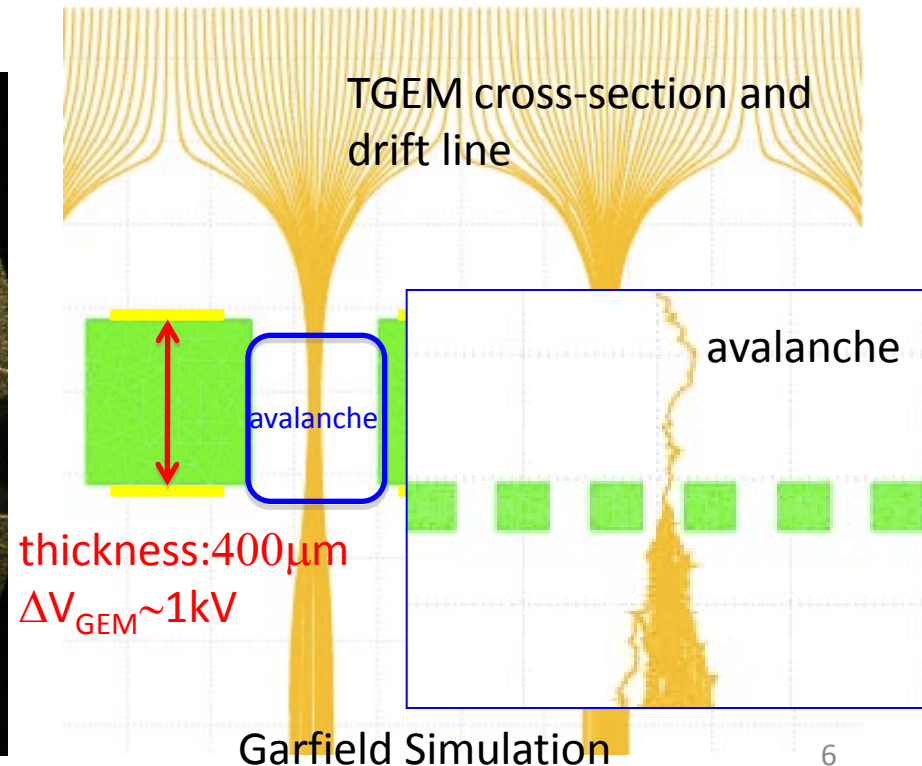
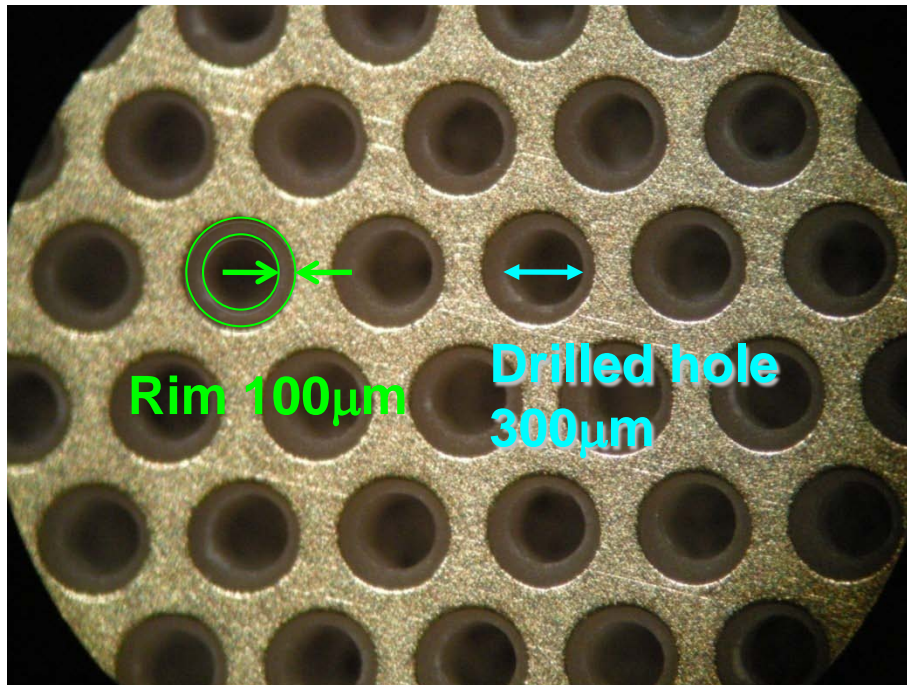
about TGEM

goal: gain $\sim 10^4$ with stable operation

What is TGEM ?

Thick-GEM is ...

- a robust, simple to manufacture, high-gain gaseous electron multiplier
- **cost-effectively fabricated from double-clad G10 plates, using standard printed circuit board (PCB) techniques**
- holes are mechanically drilled (and, if necessary, the hole's rim is chemically etched to prevent discharges)
- easy to operate and feasible to cover large areas, compared to the standard foil GEM



TGEM in JAPAN

Produced by REPIC Co.

● **RIKEN & TITECH**

t~400 μ m, C, Cu electrode
@ P10, NTP

● **Tsukuba U. & CNS &
Osaka Electro-Communication U.**

t~400 μ m, Cu electrode
@ He/CO₂, low presser (~0.1atm)

● **Osaka Electro-Communication U.**

t~400 μ m, Cu electrode
@ P10, NTP

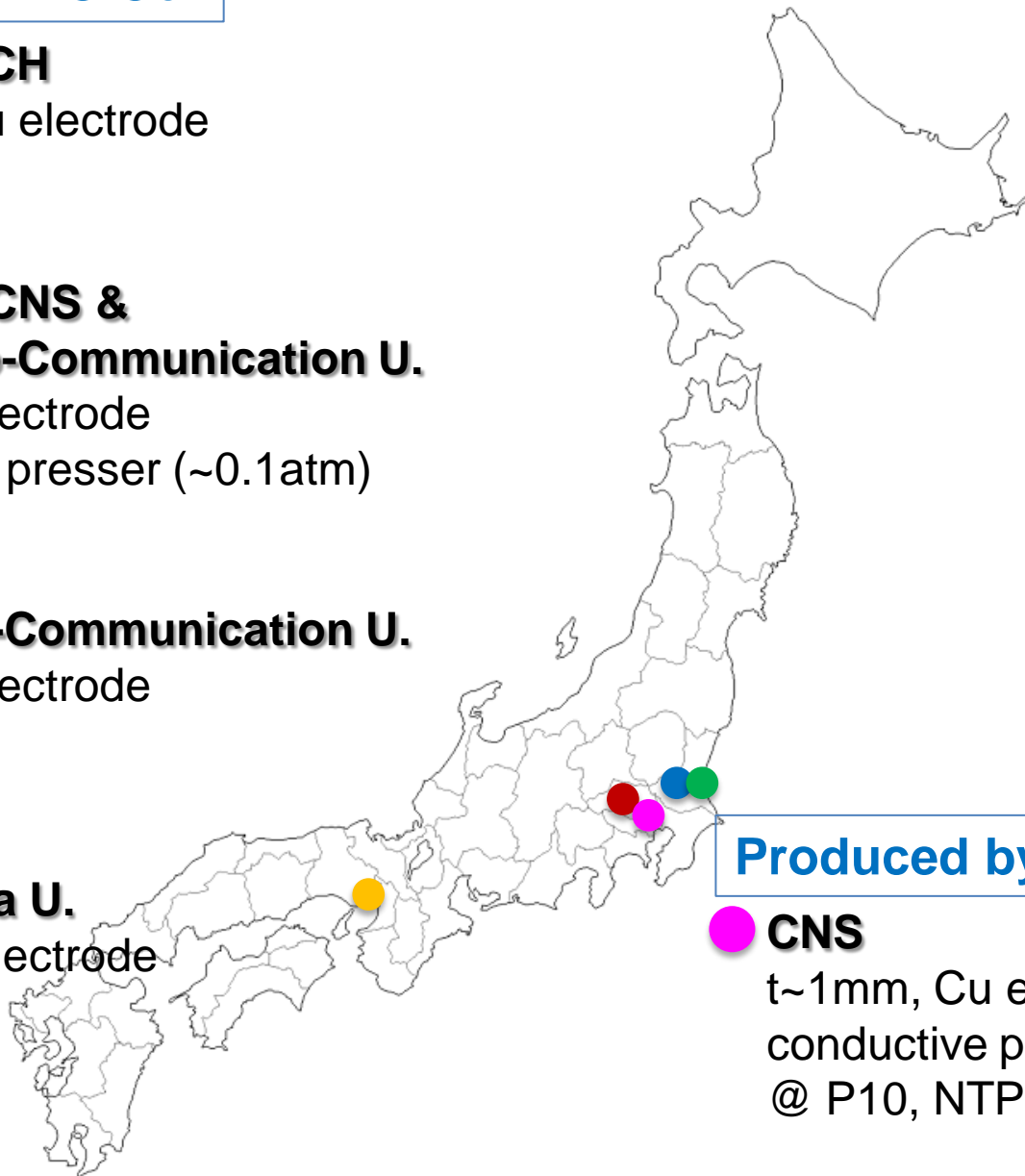
● **KEK & Waseda U.**

t~400 μ m, Cu electrode
@ Ar, ~90K

Produced by Scienergy Co.

● **CNS**

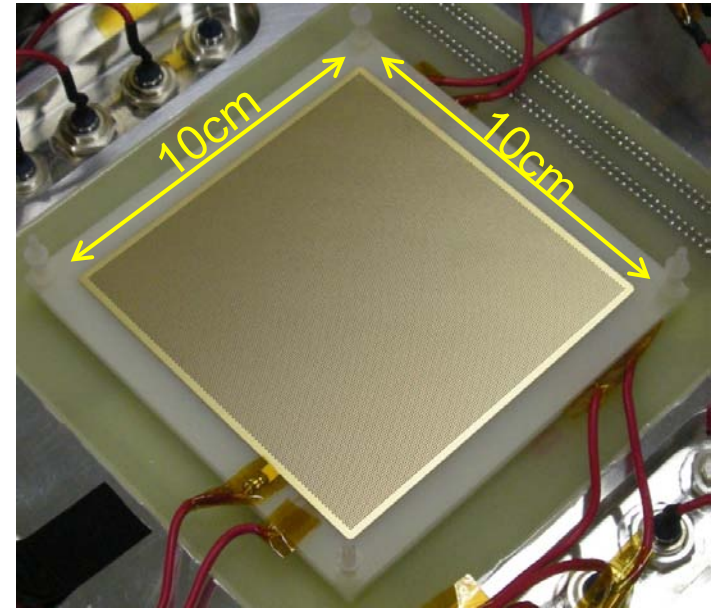
t~1mm, Cu electrode,
conductive polymer electrode
@ P10, NTP



TGEM prototypes

goal

- gain $\sim 10^4$ @ P10, NTP (double TGEMs)
- stable operation for a month, with gain fluctuation within \sim a few ten % for a month & a few % for a day



many groups have reported TGEMs work successfully, but actually **it's NOT so easy to operate TGEM with high gain stably!**

- they use small TGEMs, e.g. $\sim 3 \times 3 \text{ cm}^2$
- most of them don't discuss stability of TGEM

We have studied basic TGEM behavior and performance.

TGEM prototypes @ RIKEN

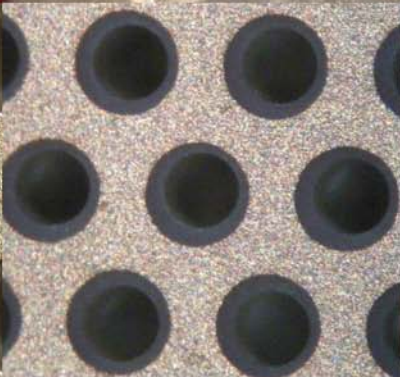
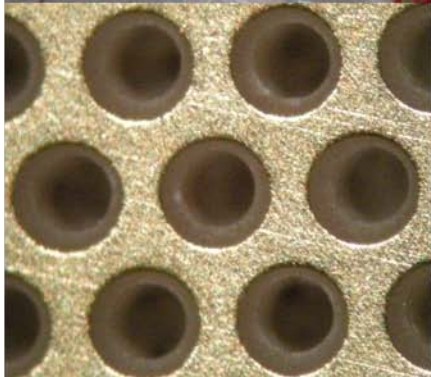
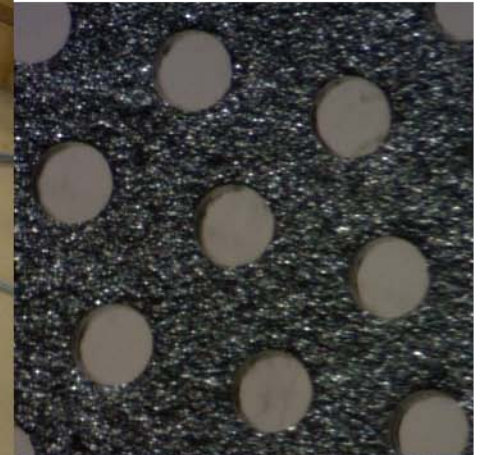
produced by REPIC corp. and TOUKAI DENSHI KOUGYOU corp.

No.	Electrode	Insulator	Thickness[μm]	Hole-diameter[μm]	Rim[μm]	
1	Cu	FR4/UV	200	300	50	× 2
2	Cu	FR4/UV	200	500	–	× 2
3	Cu	FR4/UV	400	300	–	× 5
4	Cu	FR4/UV	400	300	30	× 2
5	Cu	FR4/UV	400	300	50	× 2
6	Cu	FR4	400	300	100	× 2
7	Cu	FR4/UV	400	500	–	× 2
8	C	FR4	400	300	–	× 4
9	C	FR4/UV	400	300	–	× 7
10	C	G10	400	300	–	× 2
11	C	CEM3	400	300	–	× 2
12	C	FR4	600	300	–	× 2
13	C/Cu	FR4/UV	400	300	–	× 4

size : 10cm x 10cm

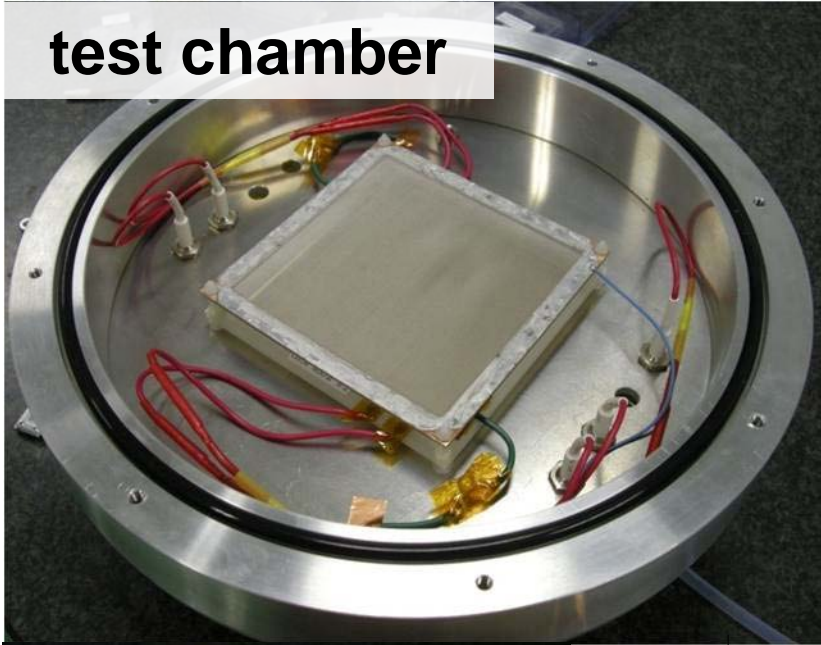
Total 40

many TGEM prototypes

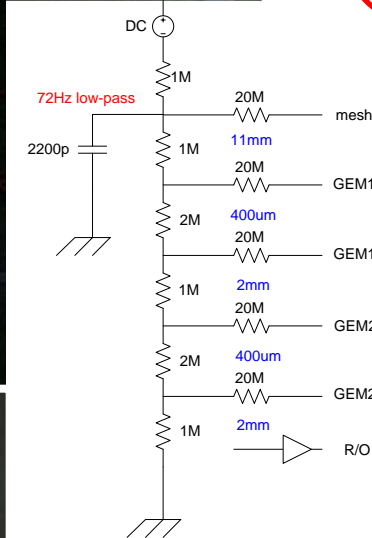
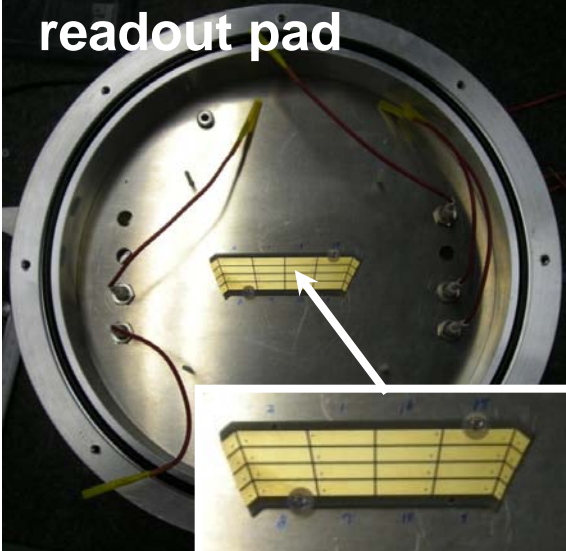


Test bench setup

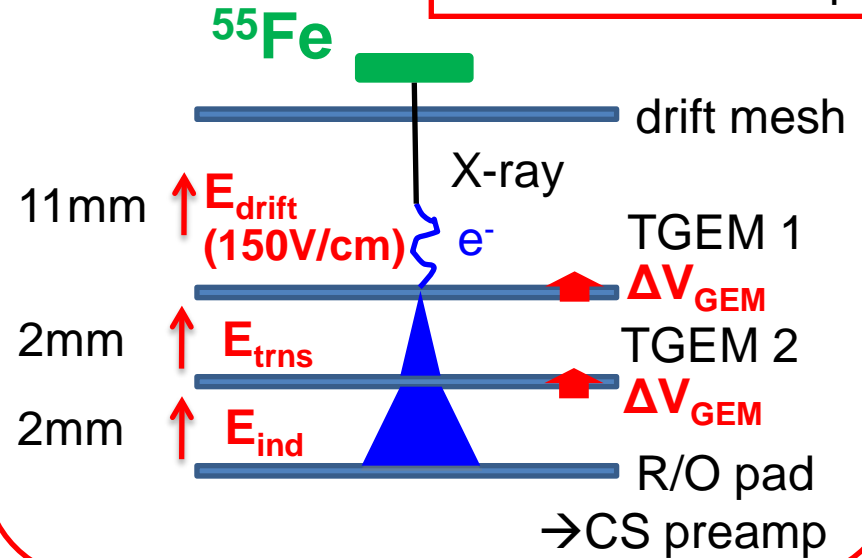
test chamber



readout pad



Double GEM setup



- double TGEMs

- Gas : P10 at 1atm, normal temperature

- HV divider with resistive chain
→ Ratio of $\Delta V_{GEM}/E_{trns}/E_{ind}$ is const.

Results of TGEMs

Cu-electrode TGEM

No.	Electrode	Insulator	Thickness[μm]	Hole-diameter[μm]	Rim[μm]	Max gain
1	Cu	FR4/UV	200	300	50	$\sim 10^3$
2	Cu	FR4/UV	200	500	-	-
3	Cu	FR4/UV	400	300	-	$\sim 10^4$
4	Cu	FR4/UV	400	300	30	over 2×10^4
5	Cu	FR4/UV	400	300	50	over 2×10^4
6	Cu	FR4	400	300	100	over 2×10^4
7	Cu	FR4/UV	400	500	-	$\sim 10^3$

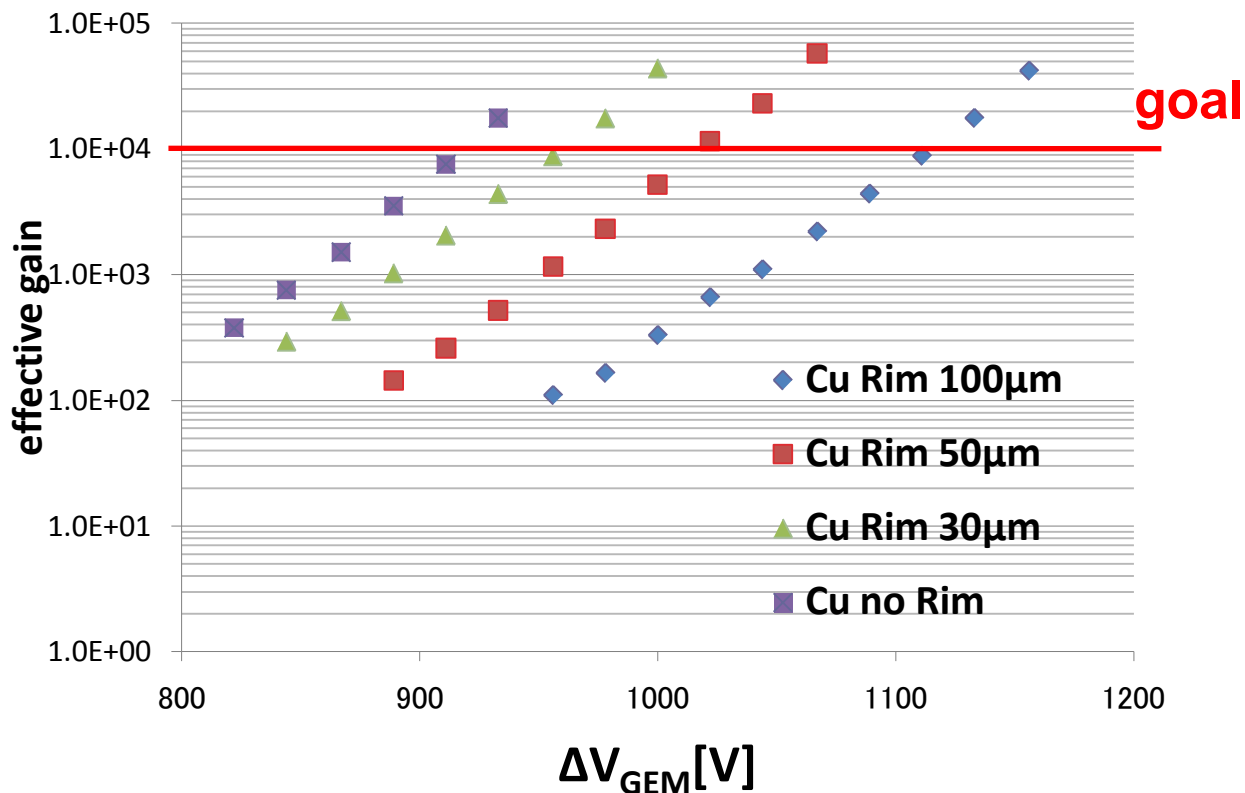
Rim of 50,100 μm : Weizmann method (drilling + masked etching)
Rim of 30 μm : CERN method (drilling + resist etching)
w/o Rim (#3) : w/ hydrogen peroxide - sulfuric acid etching

TGEMs with thickness of 400 μm and hole diameter of 300 μm achieve maximum gain of 10^4

dependence on rim size

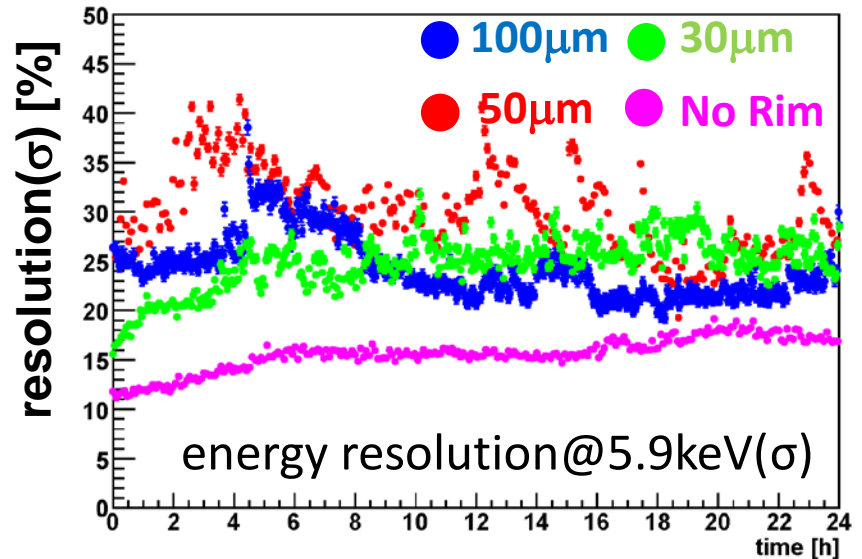
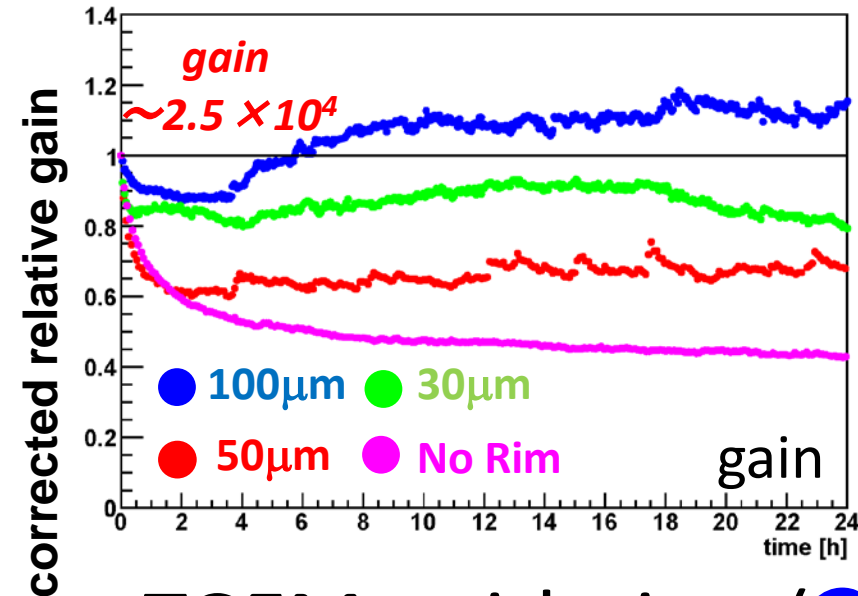
the limits of gain around 10^5 is caused by reather limit (source = ^{55}Fe).

$E_{\text{drift}} = 150\text{V/cm}$		
ΔV_{GEM} (V)	: E_{trans} (V/cm)	: E_{induct} (V/cm)
1	: 2.5	: 7.5



TGEM with larger rims requires higher voltage, but enables higher gain

gain and resolution stability (24h)

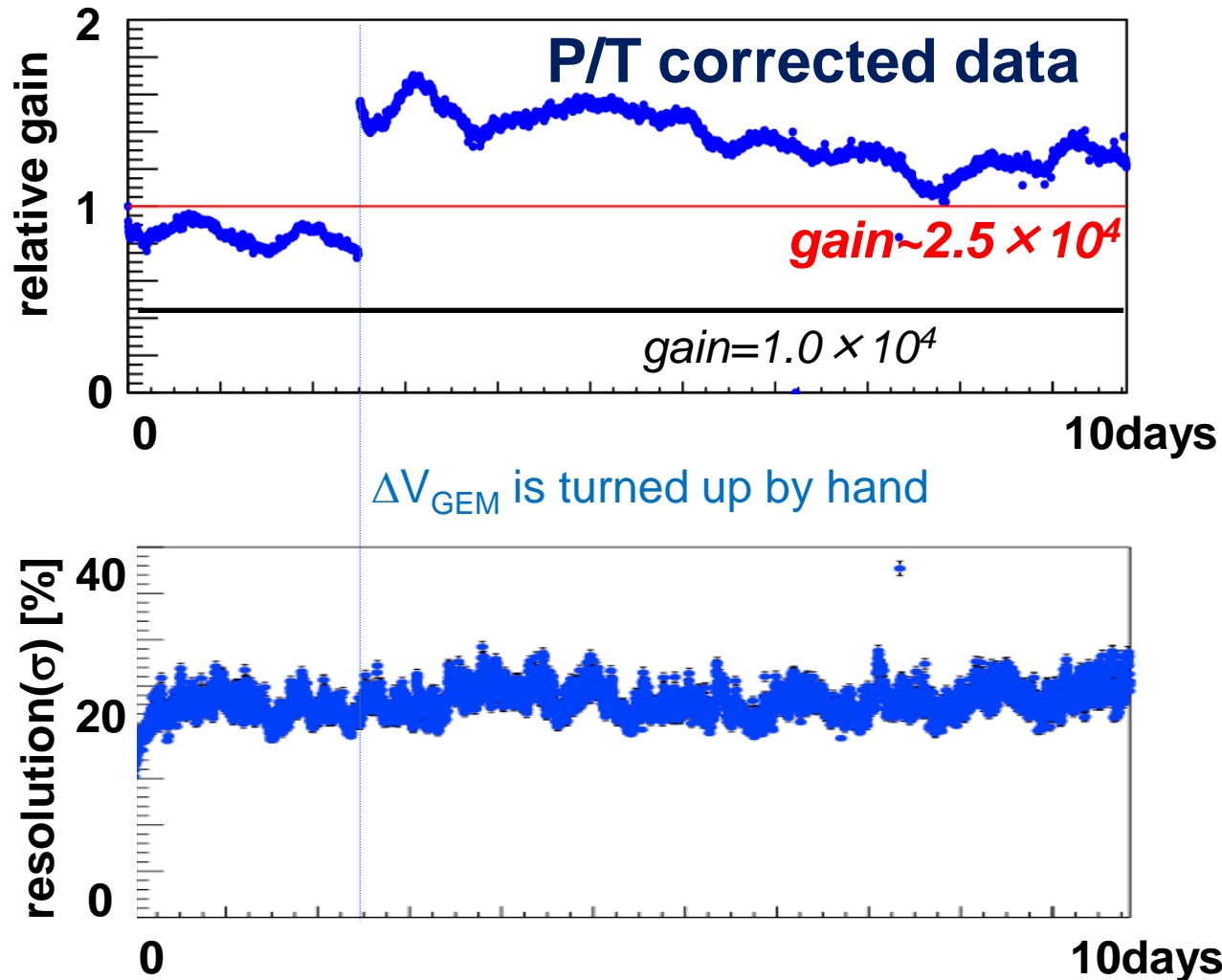


TGEMs with rims (●, ●, ●) are **NOT so stable**
TGEM without rims (●) is **stable**

- initial drop of gain is caused by charge-up (polarization?) of the insulator?
- instability of TGEMs with rims is caused by charge-up of the insulator not metalized.
- mismatch of the center of the etched and drilled holes and incomplete round-shape of rims cause the instability.



long term stability (**30 μ m rims TGEM**, 10days)



- TGEM with 30 μ m rims can be operated with gain of more than 10^4 for the long term @ P10, NTP
- gain stability is within $\sim 50\%$ /week & $\sim 10\%$ /day

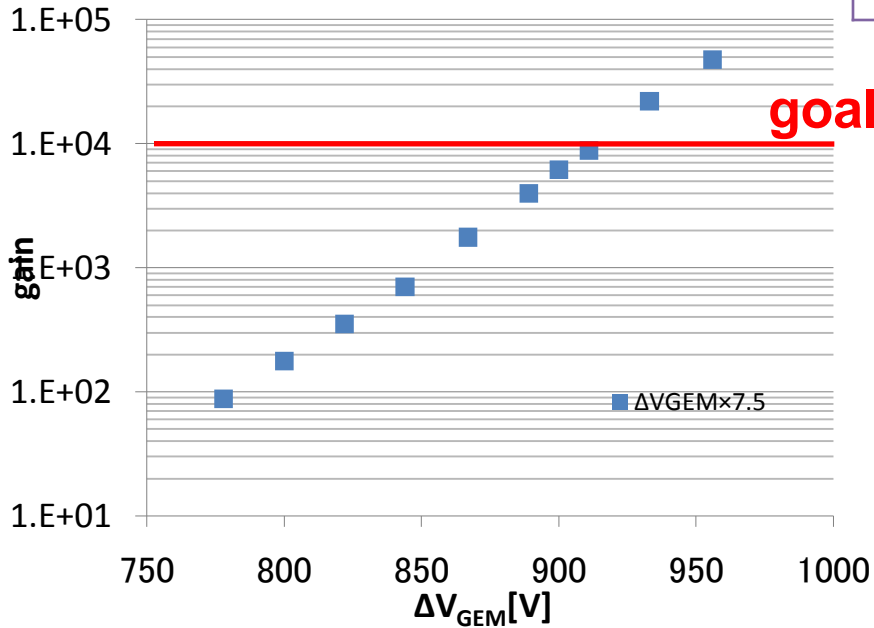
C-electrode TGEM

- To avoid the effects of rims, we are developing a new resistive-electrode TGEM (RETGEM) which has electrodes coated with **graphite paint**.
- RETGEMs have an advantage of being fully spark-protected.

No.	Electrode	Insulator	Thickness[μm]	Hole-diameter[μm]	Rim[μm]	Max gain
8	C	FR4	400	300	–	over 2×10^4
9	C	FR4/UV	400	300	–	–
10	C	G10	400	300	–	$\sim 10^3$
11	C	CEM3	400	300	–	over 2×10^4
12	C	FR4	600	300	–	$\sim 10^2$

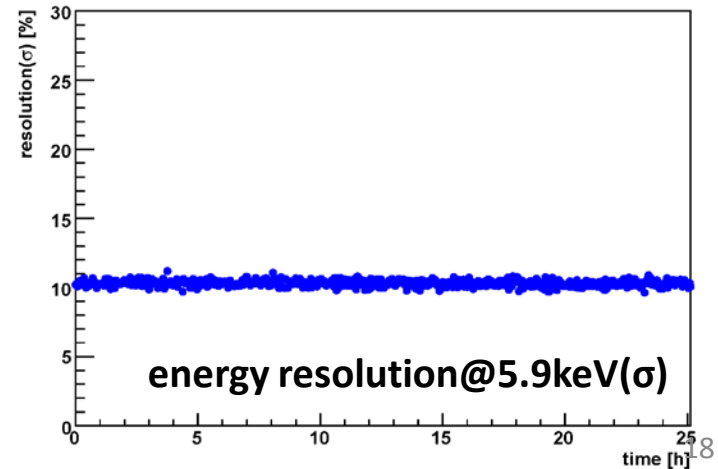
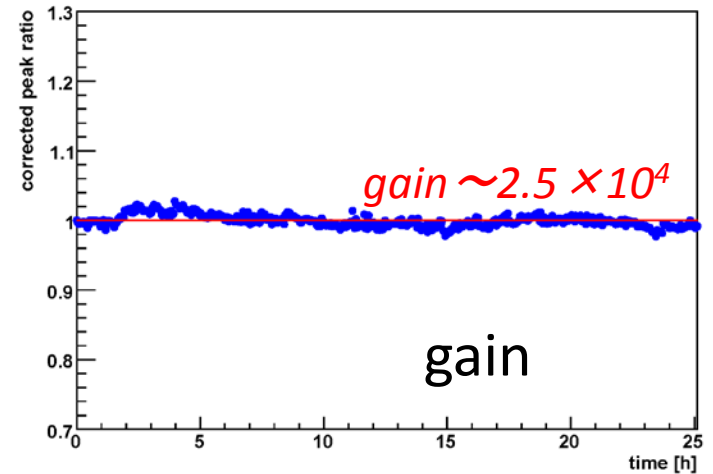
Results of the first sample

Carbon



$E_{drift} = 150 \text{ V/cm}$

ΔV_{GEM} (V)	:	E_{trans} (V/cm)	:	E_{induct} (V/cm)
1	:	2.5	:	7.5

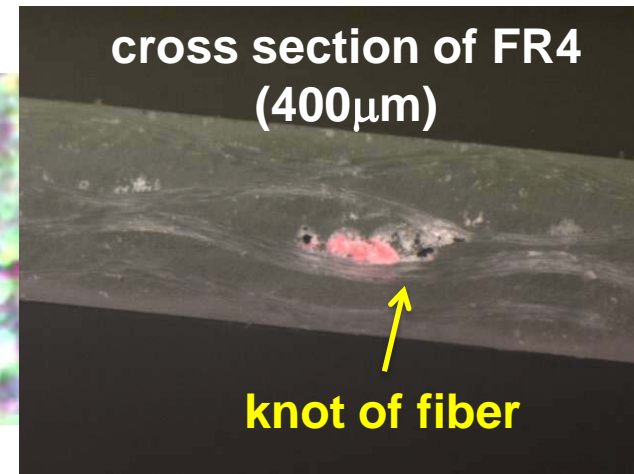


It seemed that C-electrode TGEMs
work excellent!!!
However...

carbon TGEMs have no reproducibility at all !!!

only first 2 out of 11 samples of RETGEMs work !!!

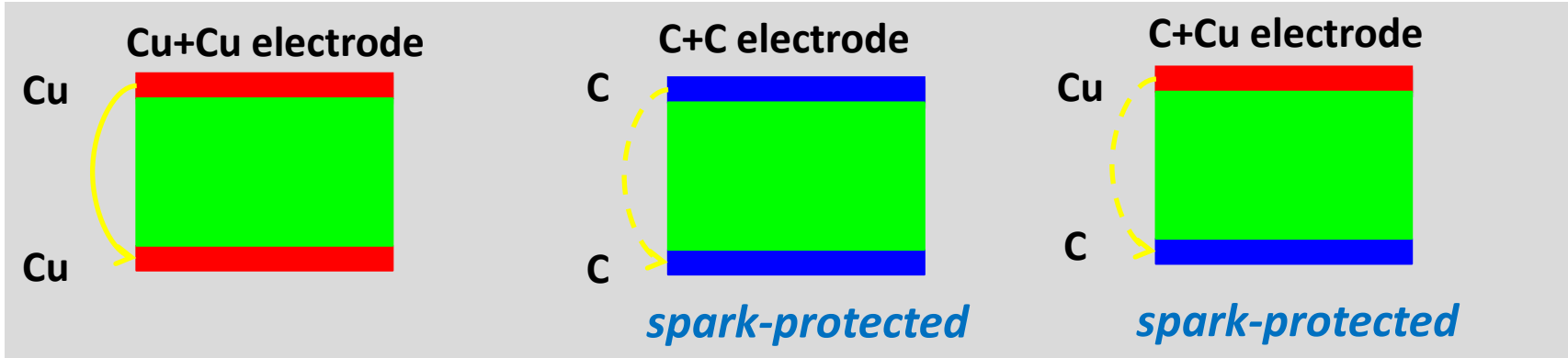
- discharge from burrs arising from drilling process
(but these can be removed using antistatic-brush)
- carbon attachment inside the holes caused by knot of FR4 fiber



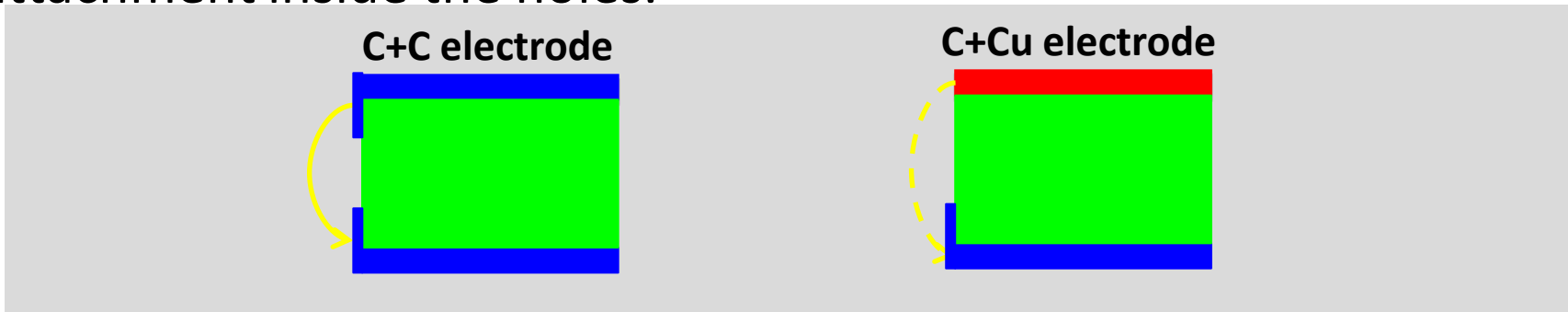
→ now, we have been studying another insulator of
CEM3 not FR4/G10

C/Cu-electrode Hybrid-TGEM

- In principle, if one side of electrode is resistive then that would be spark-protected.



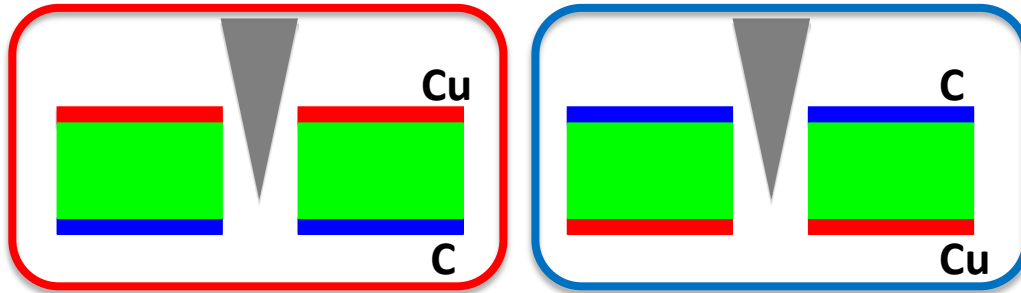
- Hybrid-TGEM would have a possibility of reduction of carbon attachment inside the holes.



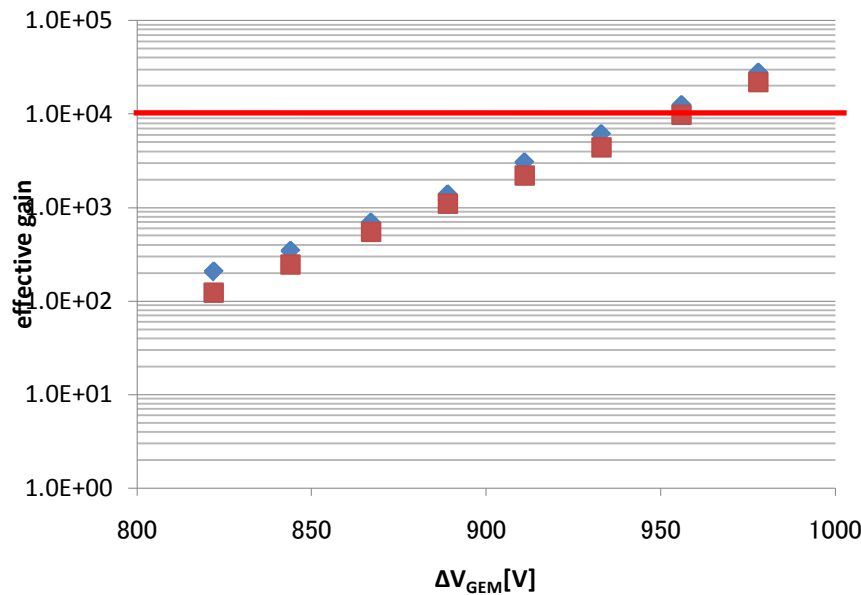
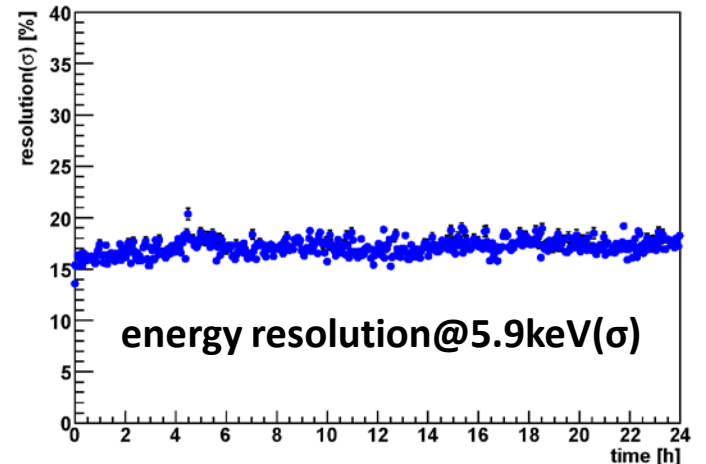
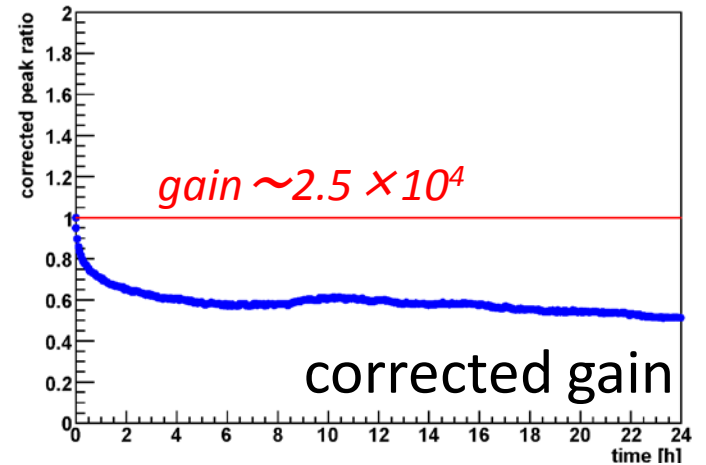
No.	Electrode	Insulator	Thickness[μm]	Hole-diameter[μm]	drill	
13	C/Cu	FR4/UV	400	300	Cu \rightarrow C	$\times 2$
	C/Cu	FR4/UV	400	300	C \rightarrow Cu	$\times 2$

Results of C/Cu-electrode Hybrid TGEM

We tried 2 drilling directions,
i.e. Cu → C and C → Cu

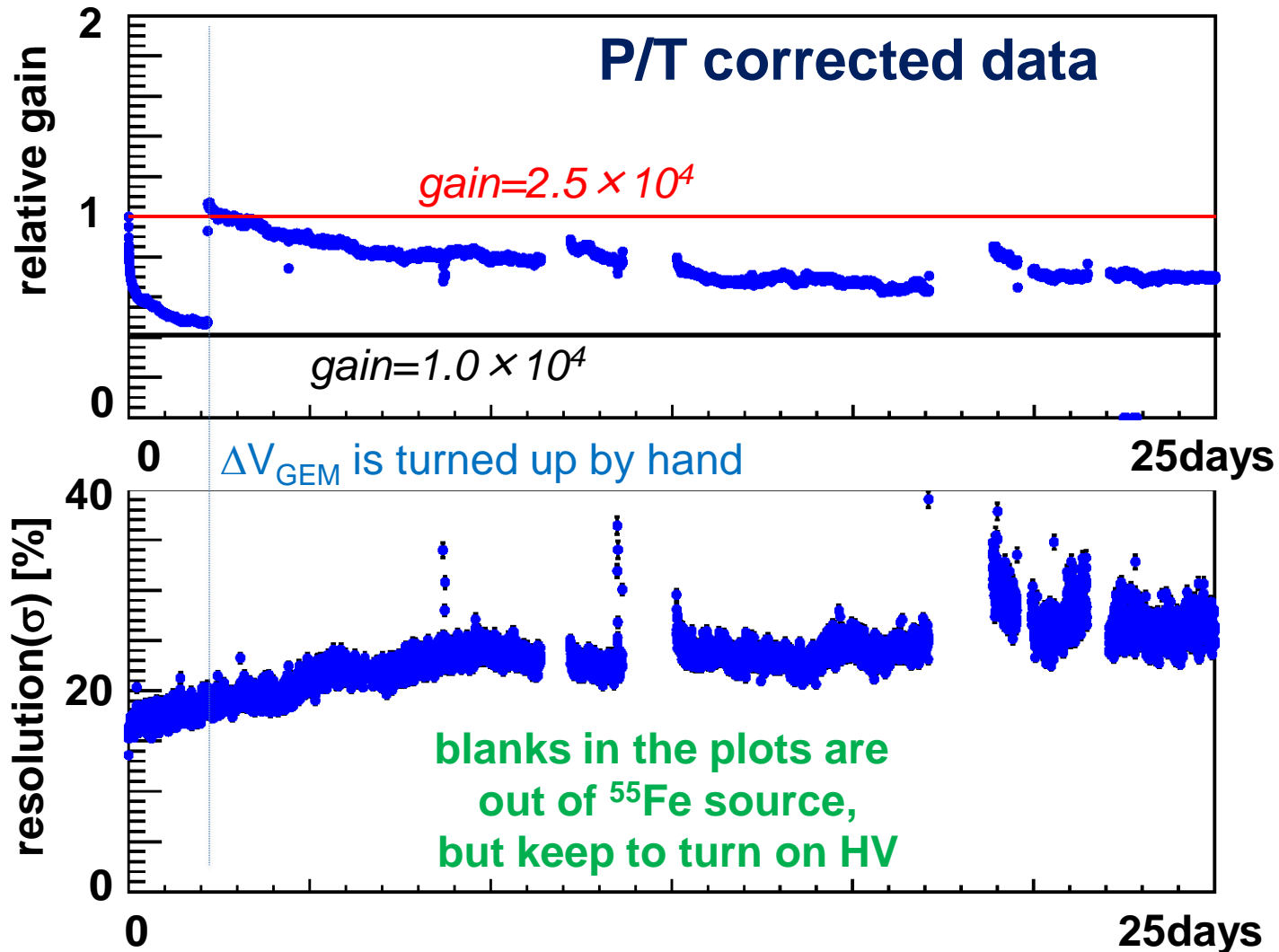


$E_{\text{drift}} = 150 \text{ V/cm}$		
$\Delta V_{\text{GEM}} \text{ (V)}$	$E_{\text{trans}} \text{ (V/cm)}$	$E_{\text{induct}} \text{ (V/cm)}$
1	2.5	7.5



The 2 fabrication methods work similarly

long term stability (hybrid TGEM, 25days)



- hybrid TGEM can be operated with more than gain of 10^4 for the long term @ P10, NTP
- gain stability is within $\sim 20\%$ /week & $\sim 5\%$ /day

Summary

- We are developing a **TGEM-TPC** for the J-PARC E15 upgrade
- **Cu electrode TGEM with 30 μ m rims** can be operated with gain of more than 10^4 for the long term rather stably @ P10, NTP
- **C-electrode TGEM** is far from goal...
- **C/Cu electrode TGEM** can be operated with gain of more than 10^4 for the long term stably @ P10, NTP

TGEM for Double-phase Ar Detector?

@ P10, NTP (with gain of $\sim 10^4$, our group)

TGEM is just starting to take off, in our group.

@ low pressure (~ 0.1 atm) and normal temperature

TGEM has worked perfectly with gain of $\sim 10^3$,
e.g. Tsukuba Univ. group.

@ pure-Ar, low temperature (~ 90 K)

It seems to be very difficult...

key points are ...

- multi-TGEM operation
- low-pressure operation(?)
- to make centered and symmetric (large) rims, completely
- ...

C electrode TGEM with CEM3 insulator

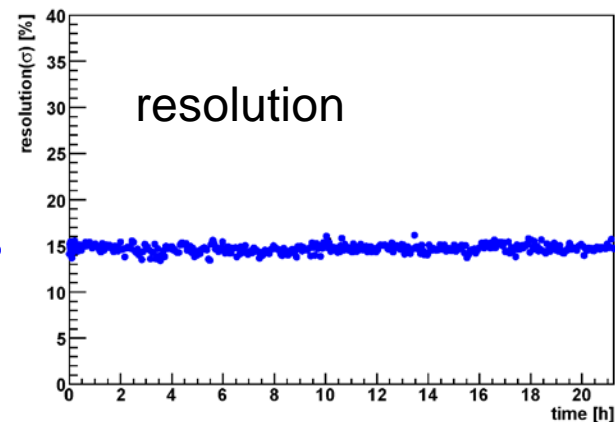
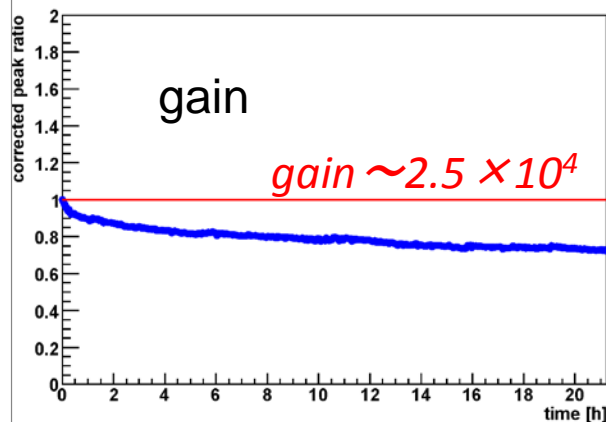
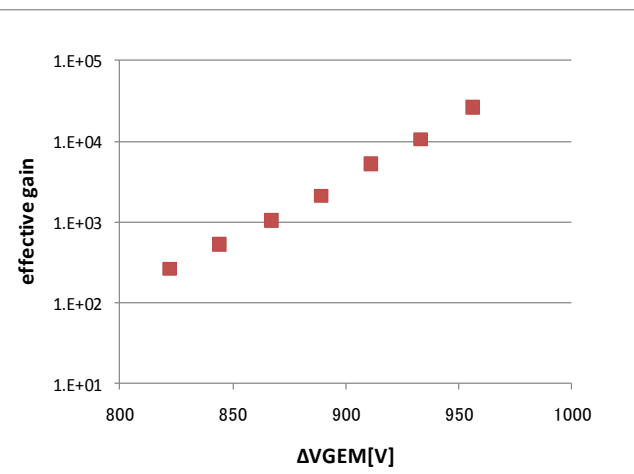
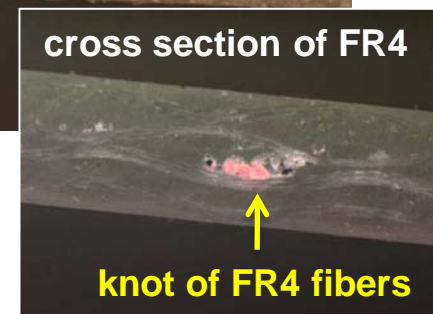
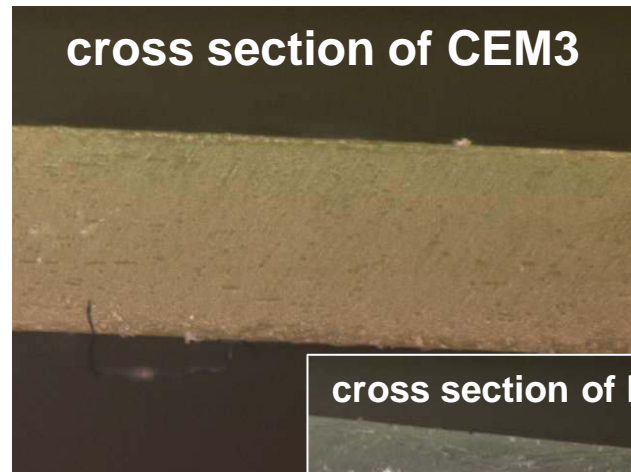
A cross section of CEM3 is very clean compared with that of FR4.



reduction of carbon attachment inside the holes

● Now we are investigating reproducibility of CEM3 RETGEM

● A disadvantage of CEM3 RETGEM is its flexibility



How to make Rims

There are 2 ways

Weizmann method

drilling + masked etching

Advantage:

large rims can be made easily

Disadvantage:

difficult to center etched and drilled holes

CERN method

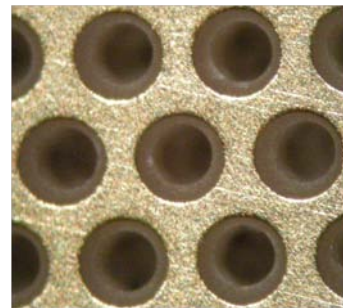
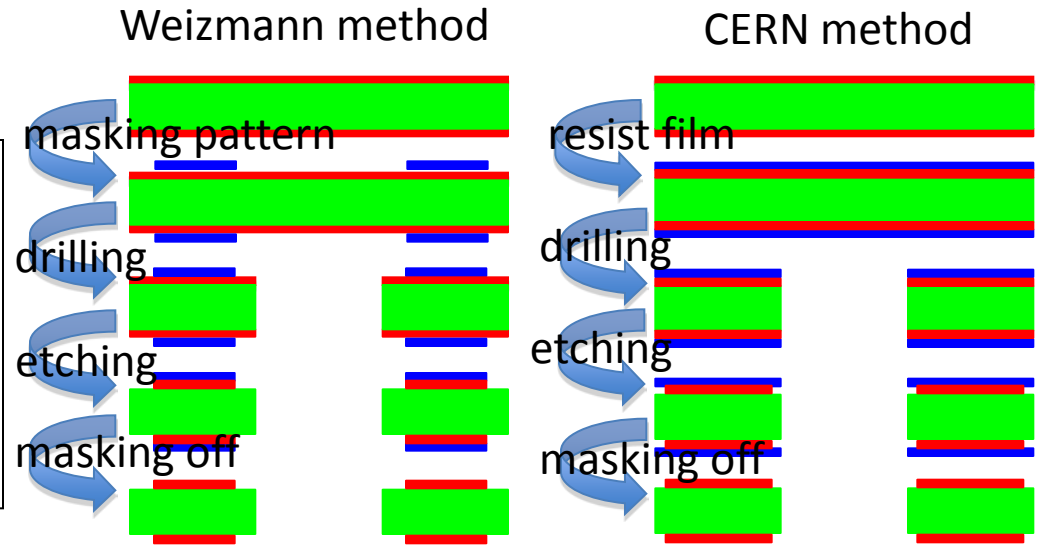
drilling + resist etching

Advantage:

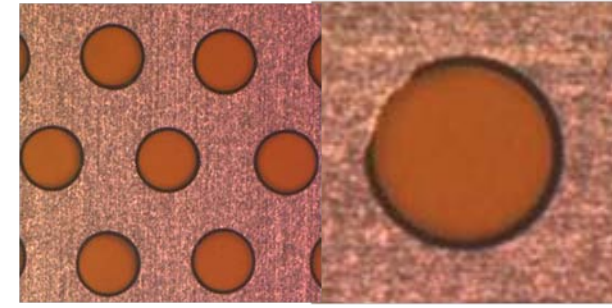
center of etched and drilled holes are the same

Disadvantage:

difficult to make large rims



Weizmann

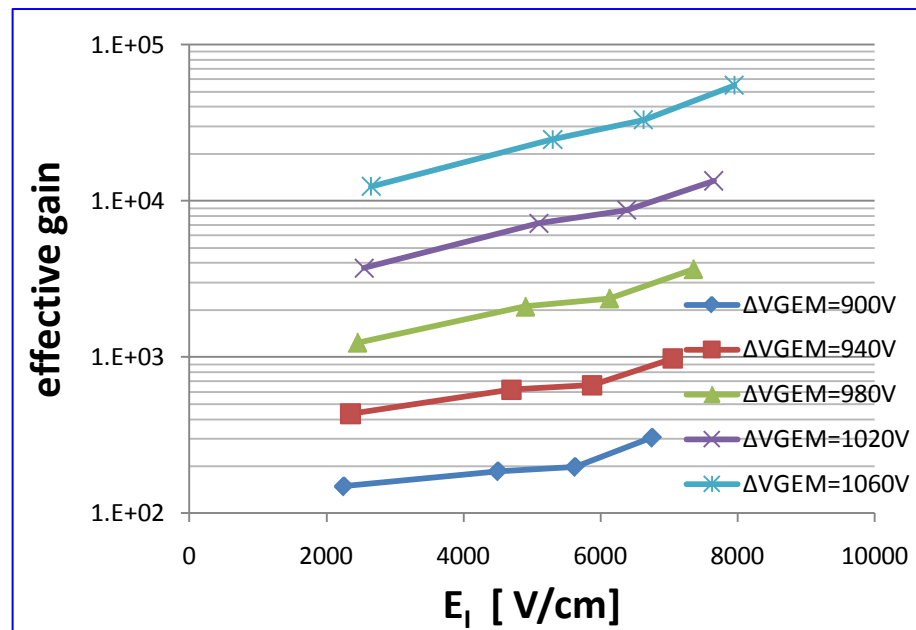
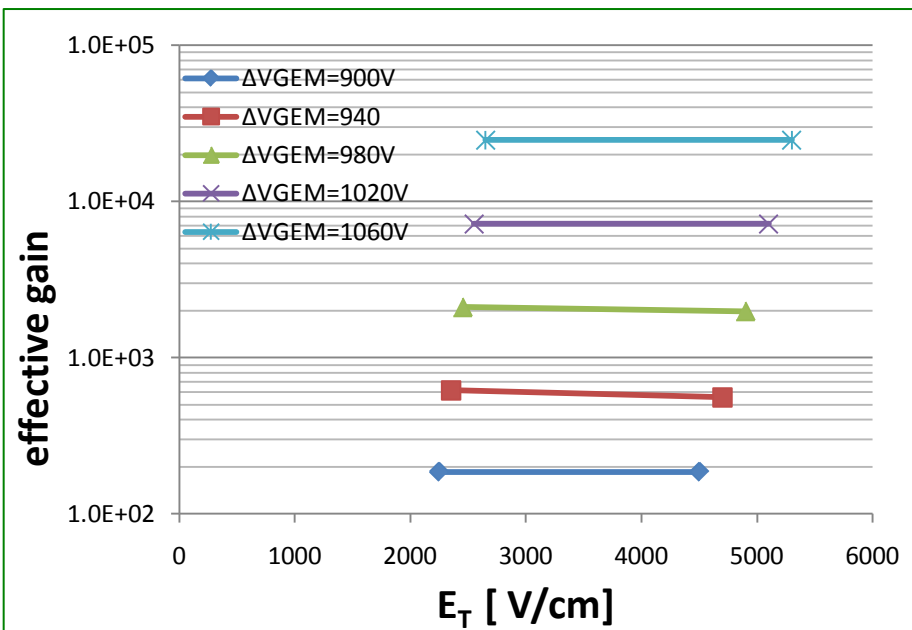
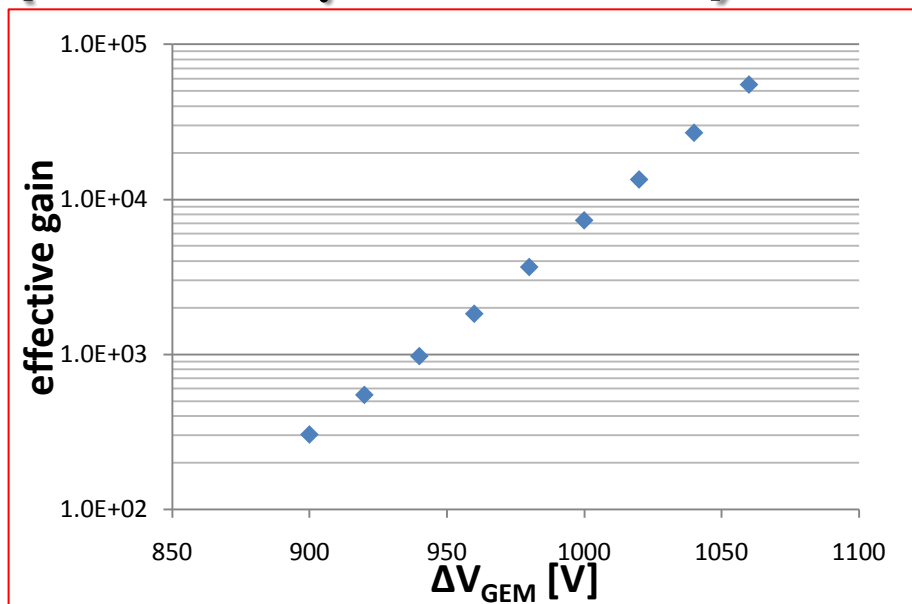
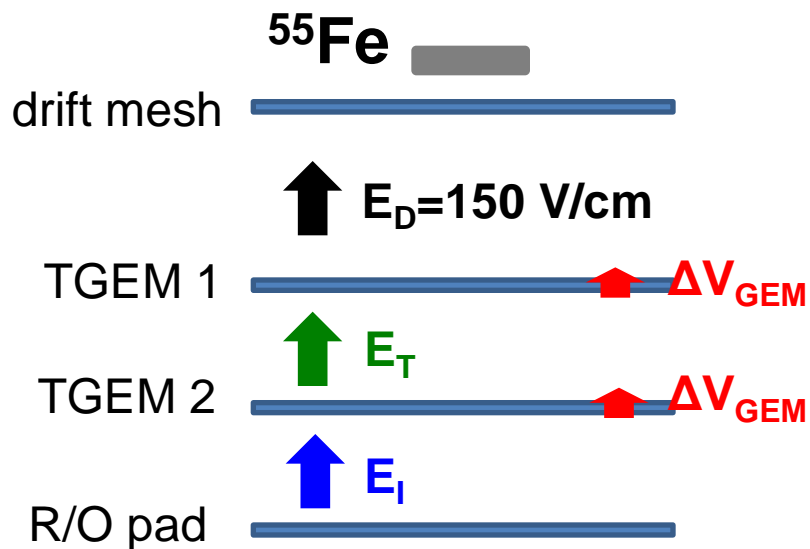


CERN

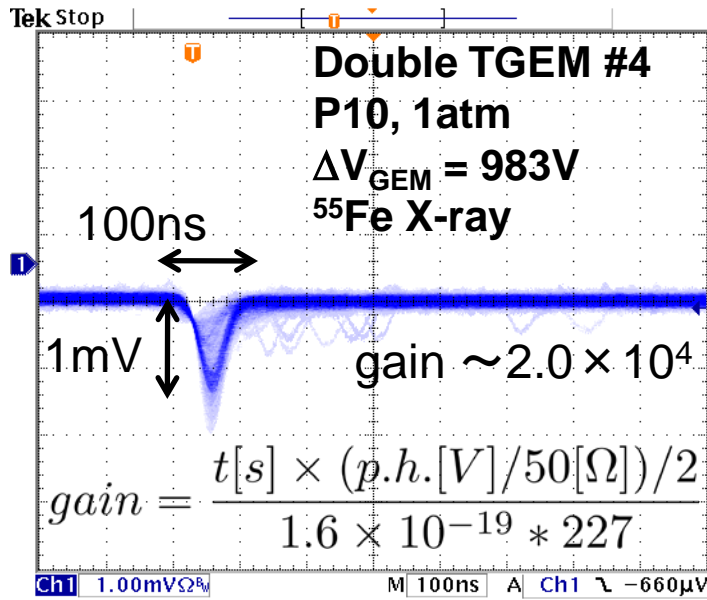
(failure)

It's known that large rims cause instability of TGEMs, although those enable TGEMs to reach high gain.

ET, EI dependence (Rim 30 μ m TGEM)

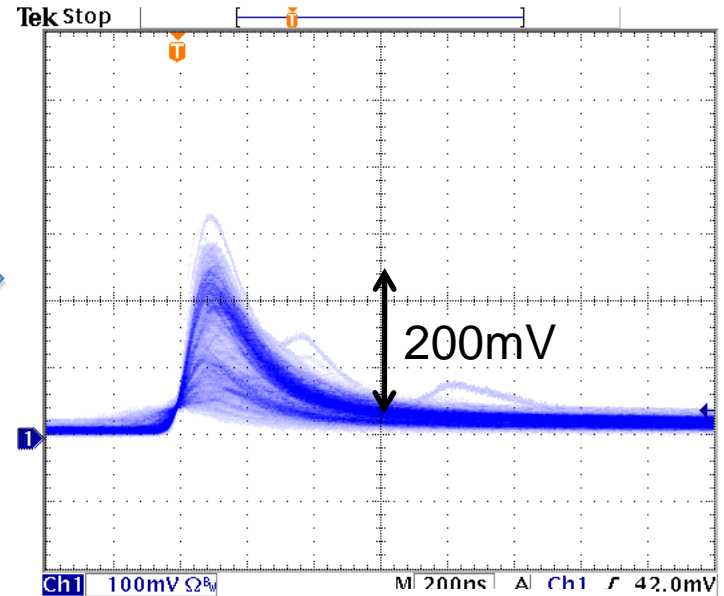


signals and goal of the studies



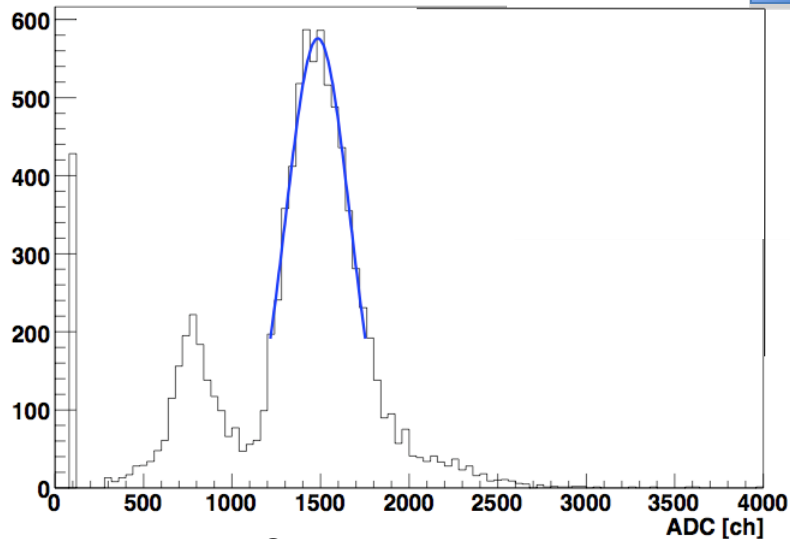
raw signal

preamp



preamp out

ADC

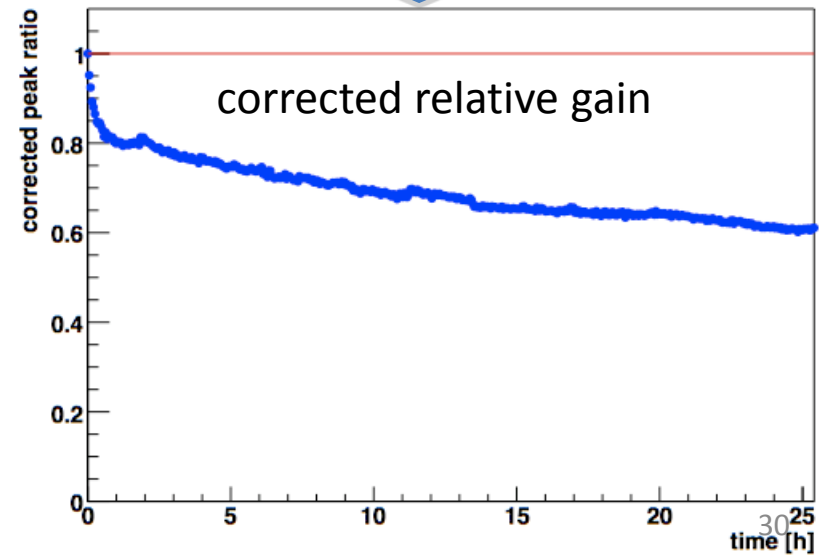
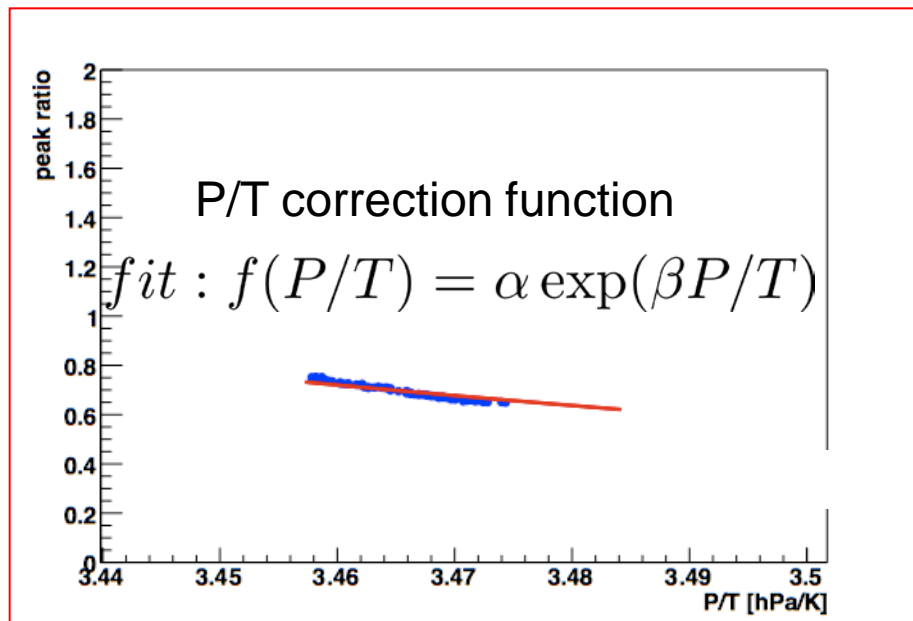
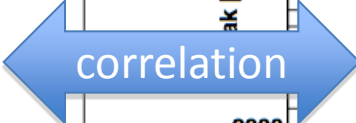
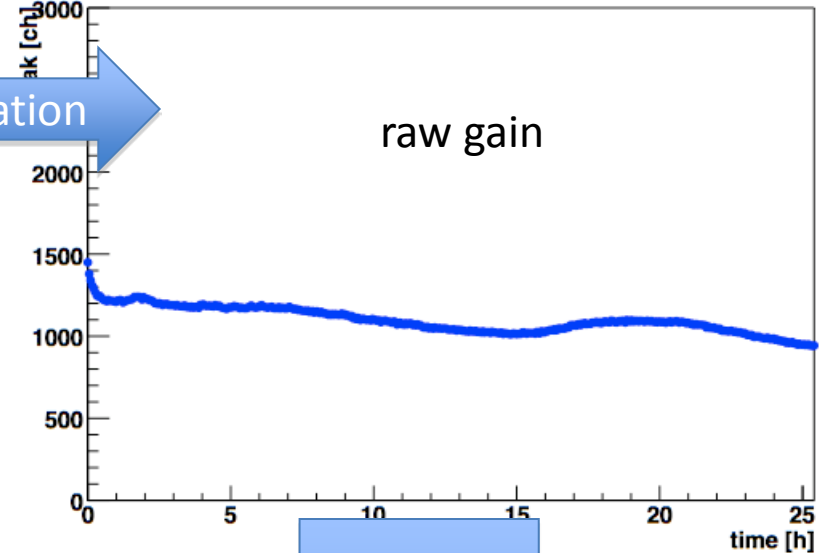
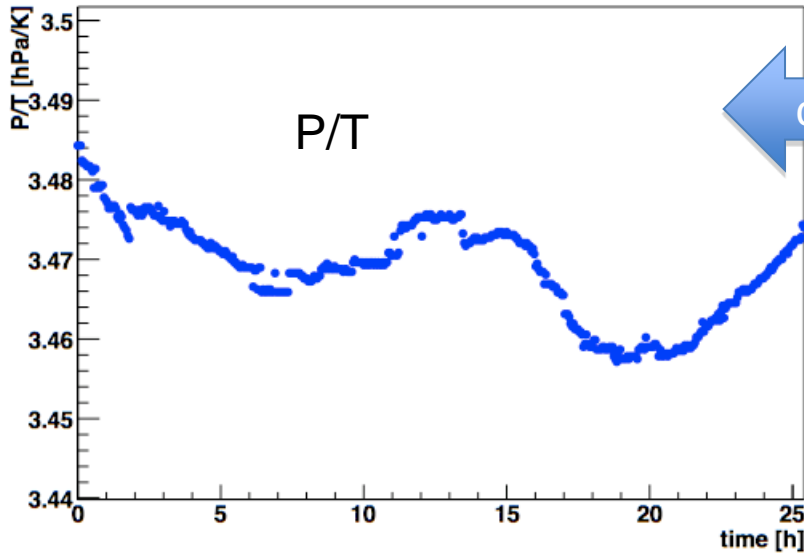


goal for of TGEM study

in consideration of TPC operation,

- effective gain $\sim 10^4$
- long time stability of gain and resolution

P/T correction of gain



after-treatment of C-electrode TGEM

We tried many items to make the C-electrode TGEMs work

- ethanol cleaning → ✕
 - does not improve at all
- plasma etching → △
 - improves a little bit, but it's not perfect
 - does not remove burrs of carbon
- removing burrs with resist-film and/or antistatic-brush → △
 - removes burrs, but does not improve
- steam cleaning → ✕
 - does not improve at all
- polyimide etching → ?
 - effects are depend on material of the insulator
 - and also depend on etching time
- change insulator (FR4/UV → CEM3) → ?
 - CEM3 TGEMs work good, but that are after polyimide etching
(we did not check the without the etching)

We have to study more

Outlook

- Nonagonal TGEMs (w/o rims and Cu-rim-30 μ m) and Hybrid-TGEMs for the TPC were produced, and studies have started now.
- Development of Carbon TGEMs will be continued in the year 2010.